

Application No. Not Yet Assigned
Paper Dated September 27, 2006
In Reply to USPTO Correspondence of N/A
Attorney Docket No. 5038-062725

IAP01 Rec'd PCT/PTO 27 SEP 2006
10/594537 Customer No. 28289

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : Not Yet Assigned
Applicants : **Ho-Seong NAM et al.**
Filed : Concurrently Herewith
Title : **CHEMICAL MECHANICAL POLISHING
SLURRY COMPOSITION FOR SHALLOW
TRENCH ISOLATION PROCESS OF
SEMICONDUCTOR**
International Application No. : PCT/KR2005/000859
International Filing Date : 24 March 2005
Priority Date(s) Claimed : 29 March 2004

MAIL STOP PCT
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Sir:

Prior to initial examination, please amend the above-identified patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 1 of this paper.

Amendments to the Abstract begin on page 5 of this paper and a replacement page is attached hereto.

Remarks begin on page 6 of this paper.